



Application Number
10/710821

Matthew J. Breitwisch, et al.

Group Art Unit
Unassigned

[illegible][illegible]

DWO		M.Q. Huda, et al., "Technique for Large Elevation of Source/Drain Using Implantation Mediated Selective Etching", <u>Electrochemical and Solid-State Letters</u> , pp. G117-G118 (2003).

DATE CONSIDERED 09/06/2006

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

IDS - 08/05/2004

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention**ISOLATED FULLY DEPLETED SILICON-ON-INSULATOR REGIONS BY
SELECTIVE ETCH**

Application Number:

Confirmation Number:

First Named Applicant: Matthew Breitwisch

Attorney Docket Number: BUR920040015US1

Search string: (5306659 or 5324683 or 5391911 or 6020250 or 6492705).pn.

US Patent Documents**Note: Applicant is not required to submit a paper copy of cited US Patent Documents**

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
DWO	1	5306659	1994-04-26	Beyer et al			
DWO	2	5324683	1994-06-08	Fitch et al			
DWO	3	5391911	1995-02-21	Beyer et al			
DWO	4	6020250	2000-02-01	Kenny			
DWO	5	6492705	2002-12-10	Begley et al			

Signature

Examiner Name	Date
/Douglas W Owens/	09/06/2006